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Examiner	Cite	Document Number	U. S. PATENT DO Publication Date	Name of Patentee or Applicant of	Pages, Columns, Lines, Where
Initials*	No.1	Number-Kind Code ^{2 (if known)}	MM-DD-YYYY	Cited Document	Relevant Passages or Relevant Figures Appear
		us- 2002/0112747 A1	8/22/2002	J. P. DeYoung, et al.	
	1.	^{US-} 2002/0088477 A1	7/11/2002	J. M. Cotte, et al.	
	1	^{US-} 2002/0055323 A1	05/09/2002	McClain et al.	
		^{US-} 2002/0026729 A1	03/07/2002	Bergman et al.	
		^{US-} 2003/0003762 A1	1/2/2003	J. M. Cotte, et al.	
		^{US-} 4,944,837	7/31/1990	M. Nishikawa, et al.	
		^{US-} 4,992,308	2/12/1991	A. K. Sunol	
		^{US-} 5,013,366	5/7/1991	D. P. Jackson, et al.	
		^{US-} 5,158,704	10/27/1992	J. L. Fulton, et al.	
		^{US-} 5,236,602	8/17/1993	D. P. Jackson	
		^{US-} 5,266,205	11/30/1993	J. L. Fulton, et al.	
		^{US-} 5,355,901	10/18/1994	R. J. Mielnik, et al.	
		^{US-} 5,370,740	12/06/1994	Chao et al.	
		^{US-} 5,377,705	1/3/1995	C. W. Smith, Jr., et al.	
		^{US-} 5,417,768	5/23/1995	C. W. Smith, Jr., et al.	
		^{US-} 5,494,526	2/27/1996	A. P. Paranjpe	
-		^{US-} 5,522,938	6/4/1996	S. O'Brien	
		^{US-} 5,533,538	7/9/1996	M. C. Marshall	
		^{US-} 5,733,964	3/31/1998	K. P. Johnston, et al.	•
		^{US-} 5,783,082	7/21/1998	J. M. DeSimone, et al.	
_	<u> </u>	^{US-} 5,789,505	8/4/1998	S. P. Wilkinson, et al.	
		^{US-} 5,866,004	02/02/1999	Houck et al.	
, , , , , , , , , , , , , , , , , , , ,		^{US-} 5,866,005	2/2/1999	J. M. DeSimone, et al.	
		^{US-} 5,868,856	2/9/1999	M. A. Douglas, et al.	
		^{US-} 5,872,257	2/16/1999	E. J. Beckman, et al.	
		^{US-} 5,873,948	2/23/1999	J-J Kim	
		^{US-} 5,908,510	6/1/1999	K. J. McCullough, et al.	
		^{US-} 5,944,996	8/31/1999	J. M. DeSimone, et al.	
		^{US-} 5,976,264	11/2/1999	K. J. McCullough, et al.	
		^{US-} 6,024,801	2/15/2000	R. M. Wallace, et al.	
		^{US-} 6,113,708	9/5/2000	G. B. Hopple, et al.	
		US- 6,176,895 B1	1/23/2001	J. M. DeSimone, et al.	
		US- 6,224,774 B1	5/1/2001	J. M. DeSimone, et al.	<u> </u>
	Ì	^{US-} 6,228,563 B1	5/8/2001	V. Starov, et al.	
		^{US-} 6,240,936 B1	6/5/2001	J. M. DeSimone, et al.	
	T	us- 6,242,165 B1	6/5/2001	B. A. Vaartstra	
	T -	US- 6,270,531 B1	8/7/2001	J. P. DeYoung, et al.	
	†	US- 6,277,753 B1	8/21/2001	W. H. Mullee, et al.	

			U. S. PATENT DO	CUMENTS	-
Examiner Initials*	Cite No.1	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or
		Number-Kind Code ^{2 (I known)}			Relevant Figures Appear
		^{US-} 6,286,231	09/11/2001	Bergman et al.	
		^{US-} 6,297,206 B2	10/2/2001	T. J. Romack, et al.	
·		^{US-} 6,306,564 B1	10/23/2001	W. H. Mullee	
		^{US-} 6,331,487 B2	12/18/2001	R. Koch	
_		^{US-} 6,333,268 B1	12/25/2001	V. Starov, et al.	
		^{US-} 6,344,243 B1	2/5/2002	J. B. McClain, et al.	
•		^{US-} 6,357,142	03/19/2002	Bergman t al.	
		^{US-} 6,403,544 B1	6/11/2002	L. B. Davenhall, et al.	
		^{US-} 6,454,869 B1	9/24/2002	J. M. Cotte, et al.	
		^{US-} 6,500,605 B1	12/31/2002	W. H. Mullee, et al.	
		^{US-} 6,506,259 B1	1/14/2003	T. J. Romack, et al.	

		FOREI	GN PATENT D	OCUMENTS		
Examiner Initials*	Cite No.1	Foreign Patent Document . Country Code ³ Number ⁴ Kind Code ⁵	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T ⁶
		EP 0 836 895 A2	4/22/1998	Europe		✓
		WO 00/16264	3/23/2000	World		1
		WO 00/26421	5/11/2000	World		1
		WO 01/21616	3/29/2001	World		4
		WO 01/32323 A1	5/10/2001	World		1
		WO 01/33613 A2	5/10/2001	World		4
		WO 01/60534 A1	8/23/2001	World		
		WO 01/87505	11/22/2001	World		1
		WO 02/11191	2/7/2002	World		4
		WO 02/15251 A1	2/21/2002	World		1
	<u> </u>	WO 02/66176	8/29/2002	World		4
		WO 84/02291	6/21/1984	World		√
		WO 99/49996	10/7/1999	World		✓
		WO 99/49998	10/7/1999	World		√
<u></u>		WO 99/61177	12/2/1999	World		4

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31/	STATEMENT BY APPLICANT (Use as many sheets as necessary)			First Named Inventor	Hoshang Subawalla, et al.	
				Art Unit		
				Examiner Name		
Sheet	3	Of	3	Attorney Docket Number	06413P USA	

	,	NON PATENT LITERATURE DOCUMENTS					
Examiner Initials*	Cite No. 1						
		K. Jackson, et al., "Microemulsions in Supercritical Hydrochlorofluorocarbons," Langmuir 12(22), pp. 5289-5295 (1996).					
		M. A. Biberger, et al., "Photoresist and Photoresist Residue Removal with Supercritical CO ₂ – A Novel Approach to Cleaning Wafers," Semiconductor Fabtech, 12th Ed., pp. 239-243.					
		D. Beery, et al., "Post Etch Residue Removal: Novel Dry Clean Technology Using Densified Fluid Cleaning (DFC)," IITC 99, pp. 140-142.					
		J. Liu, et al., "Investigation of Nonionic Surfactant Dynol-604 Based Reverse Microemulsions Formed in Supercritical Carbon Dioxide," Langmuir 17, pp. 8040-8043 (2001).					
		K. Jackson, et al., "Surfactants and Microemulsions in Supercritical Fluids," Supercritical Fluid Cleaning, pp. 87-120.					
_		R. A. Bowling, et al., "Future Challenges for Cleaning in Advanced Microelectronics," Texas Instruments slides.					
		H. J. Martinez, et al., "SCCO ₂ – Is it an Enabling Technology for the 90nm Node and Beyond?" International SeMatech slides (2002).					
		S. Pawat, "Novel Wafer Clean Technologies," International SeMatech slides (2001).					
		T. Hurd, et al., "scCO ₂ Cleaning Applications in Porous ULK Processing," Texas Instruments slides.					
		G. L. Weibel, et al., "Supercritical CO ₂ in Microelectronics Processing," Cornell University slides.					
		J. B. Rubin, et al., "Precision Cleaning of Semiconductor Surfaces Using Carbon Dioxide-Based Fluids," Clarkson University, pp. 1-26.					
· -		G. Weibel, "Supercritical CO ₂ for Semiconductor Applications," Semiconductor Equipment and Materials International (2001).					
		J. Malloy, et al., "GC Analysis of Solvent Wash Samples," Air Products and Chemicals, Inc. (2003).					
		Carpenter, B.A. et al., Supercritical Fluid Extraction and Chromatography, ACS Symposium Series 366, April 5-10, 1987, Denver, CO					
		Devittori, C. et al., Article at http://mpi.powerultrasonics.com/cleaning-co2,html , "Multifrequency ultrasonic Actuators with Special Application to Ultrasonic Cleaning in Liquid and Supercritical CO2"					
		Enokida, Y. et al., "Ultrasound-Enhanced Dissolution of UO2 in Supercritical CO2 Containing a CO2-Philic Complexant of Tri-n-Butylphosphate and Nitric Acid", <i>Industrial & Engineering Chemistry Research</i> , (2002), 41 (9), pp.2282-2286					

Examiner	Date	
Signature	Considered	

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